

## PATENT ABSTRACTS OF JAPAN

(11)Publication number : 08-337405

(43)Date of publication of application : 24.12.1996

(51)Int.Cl.

C01B 15/013  
C02F 1/42

(21)Application number : 07-149032

(71)Applicant : SUMITOMO CHEM CO LTD

(22)Date of filing : 15.06.1995

(72)Inventor : ICHIKI NAOKI  
TAGUCHI SATOSHI  
MURAKAMI SHINICHI**(54) METHOD FOR REFINING HYDROGEN PEROXIDE WATER****(57)Abstract:**

**PURPOSE:** To obtain hydrogen peroxide water of high purity which is extremely low in the concn. of metal components which are impurities and is most adequately usable for a process for producing semiconductors by bringing ion exchange resins used for refining of the hydrogen peroxide water into contact with an aq. mineral acid soln. of high purity and ultra-pure water, thereby pretreating these resins.

**CONSTITUTION:** Strongly acidic cation exchange resins and/or strongly basic anion exchange resins are used as the ion exchange resins. The concn. of the metal component of the high-purity aq. mineral acid soln. is specified to  $\leq 50.1$ ppb and the concn. of the metal component of the ultra-pure water to  $\leq 0.1$ ppb. The hydrogen peroxide water industrially produced by an anthraquinone method, etc., is usable as the crude hydrogen peroxide water used for refining. A column liquid path method is preferable in terms of working efficiency for the contact treatment of the ion exchange resins. The liquid pass velocity is specified to 0.1 to 50hr<sup>-1</sup>, the amt. of the high-purity mineral acid used for the pretreatment to  $\geq 50$  times the resin amt. and the volume of the ultra-pure water is specified to  $\geq 10$  times the resin amt. The contact temp. is specified to  $\leq 30^{\circ}$  C.

**LEGAL STATUS**

[Date of request for examination] 17.06.1998

[Date of sending the examiner's decision of rejection]

[Kind of final disposal of application other than the examiner's decision of rejection or application converted registration]

[Date of final disposal for application]

[Patent number]

[Date of registration]

[Number of appeal against examiner's decision of rejection]

[Date of requesting appeal against examiner's decision of rejection]

[Date of extinction of right]

Copyright (C); 1998,2000 Japanese Patent Office